

# Press Release

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## Oxford Instruments announces multiple system orders for Diamond Like Carbon (DLC) process applications



Oxford Instruments Plasmalab®System133 configured cluster tool

Oxford Instruments Plasma Technology (OIPT), a leading manufacturer of high technology tools and systems, has recently received multiple orders with a total value of over £3.5M for its advanced Plasmalab®System133 cluster tool. These systems will be used for the deposition of Diamond Like Carbon (DLC) – a process used in the manufacture of power devices. DLC coatings have the right electrical resistivity to make high power semiconductors work at ever higher voltages and OIPT was one of the first companies to prove this process in 1995, successfully transferring the process from the laboratory to large scale production. OIPT's range of production tools offer excellent uniformity, reproducibility and high-throughput processes, offering both single wafer or cassette load wafer handling options with integrated process control, making them ideally suited for this application.

The power semiconductor industry for automotive, industrial electronics, robotics and process automation demands chips which can carry more power, with greater reliability.

Mark Vosloo, Oxford Instruments Plasma Technology's Sales Director comments, 'Our many years of expertise in the DLC process based on our System133 cluster tool, ensures that we can meet demanding customer requirements. The company's proven process capability and reliable tailor made solutions, for these and many other challenging processes and market applications, is the reason we are the manufacturer of choice for these customers.'

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Issued for and on behalf of Oxford Instruments Plasma Technology Limited



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## **Notes to editors**

### **About Oxford Instruments plc**

Oxford Instruments designs, supplies and supports high-technology tools, processes and solutions with a focus on physical science, bioscience, environmental and industrial research and applications. It provides solutions needed to advance fundamental nanoscience research and its transfer into commercial nanotechnology applications. Innovation has been the driving force behind Oxford Instruments' growth and success for over 40 years, and its strategy is to effect the successful commercialisation of these ideas by bringing them to market in a timely and customer-focused fashion.

The first technology business to be spun out from Oxford University over forty years ago, Oxford Instruments is now a global company with over 1,300 staff worldwide and a listing on the London Stock Exchange (OXIG). Its objective is to be the leading provider of new generation tools and systems for the Physical Science and Bioscience sectors.

This involves the combination of core technologies in areas such as low temperature and high magnetic field environments, Nuclear Magnetic Resonance, X-ray electron and optical based metrology, and advanced growth, deposition and etching. Our products, expertise, and ideas address global issues such as energy, environment, terrorism and health and are part of the next generation of telecommunications, energy products, environmental measures, security devices, drug discovery and medical advances.

### **About Oxford Instruments Plasma Technology**

Oxford Instruments Plasma Technology offers flexible, configurable process tools and leading-edge processes for the precise, controllable and repeatable engineering of micro- and nano-structures. Our systems provide process solutions for nanometre layer epitaxial growth of compound semiconductor material, etching of nanometre sized features and the controlled growth of nanostructures. These solutions are based on core technologies in plasma-enhanced deposition and etch, ion-beam deposition and etch, atomic layer deposition and hydride vapour phase epitaxy. Products range from compact stand-alone systems for R&D, through batch tools and up to clustered cassette-to-cassette platforms for high-throughput production processing.